

Title (en)  
METALLURGICAL IMPACT PAD

Title (de)  
METALLURGISCHER AUFPRALLBLOCK

Title (fr)  
PLAQUE D'AMORTISSEMENT MÉTALLURGIQUE

Publication  
**EP 2205769 A1 20100714 (EN)**

Application  
**EP 08837773 A 20081003**

Priority  
• US 2008078748 W 20081003  
• EP 07253972 A 20071008  
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Abstract (en)  
[origin: EP2047928A1] An impact pad 20, formed from a refractory material capable of withstanding contact with molten metal, comprises a base 12 serving in use as an impact surface for molten metal, and a sidewall 14 extending generally upwardly therefrom. The sidewall 14 terminates at an upper surface 16 which is above the base 12 in use such that the base 12 and sidewall 14 define a receptacle for receiving molten metal. The sidewall 14 contains therein at least one channel 22, the at least one channel 22 having first and second ends 24, 26; the first end 24 being relatively closer to the base 12 at its intersection with the sidewall 14 than the second end 26. The at least one channel 22 being open ended at the second end 26 or tapering such that the at least one channel 22 has zero depth at its second end 26. The invention also relates to a tundish including an impact pad 20 as described above.

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